

A Steep-Slope Transistor Combining Phase-Change and Band-to-Band-Tunneling to Achieve a sub-Unity Body Factor

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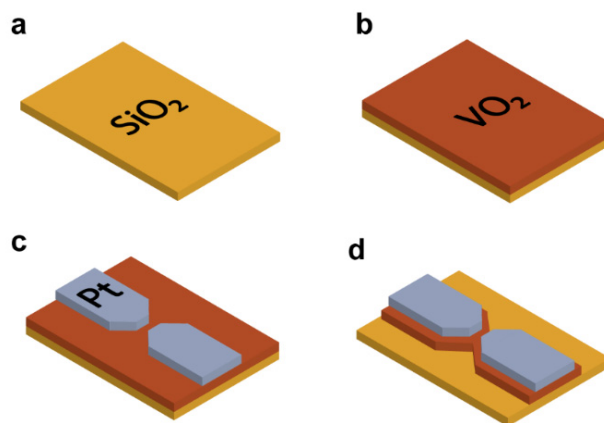
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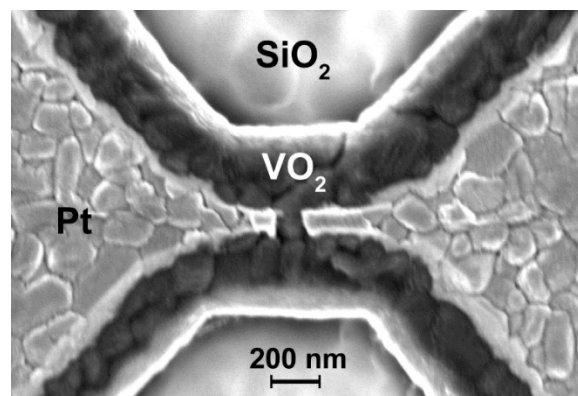
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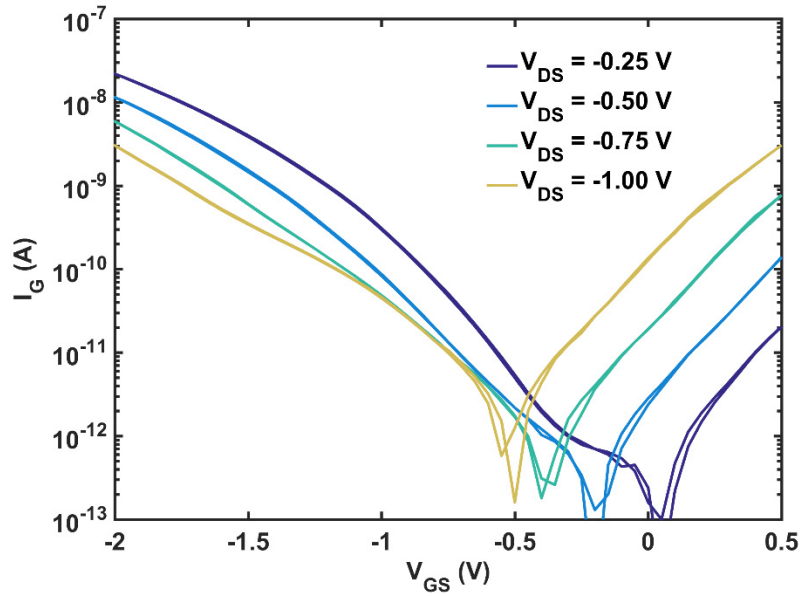
Supplementary Figures



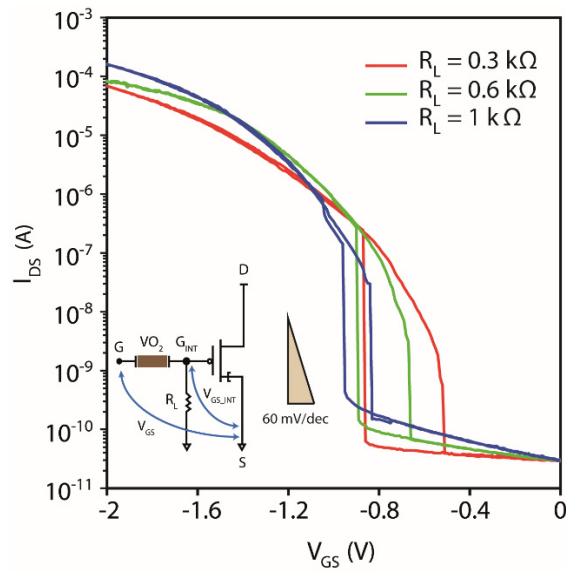
Supplementary Figure 1 | Fabrication Process of VO₂ devices. (a) VO₂ devices are fabricated starting from a silicon substrate with a thermal silicon oxide layer of 200 nm on top. (b) A 200 nm thick VO₂ layer is deposited with reactive sputtering of a Vanadium target in an O₂/Ar plasma at 600 °C substrate temperature. (c) Switch electrodes are defined via electron beam lithography on PMMA/MMA and lift-off of a 100 nm thick Platinum film. (d) VO₂ is removed around the switch area using electron beam lithography on ZEP and ion beam etching.



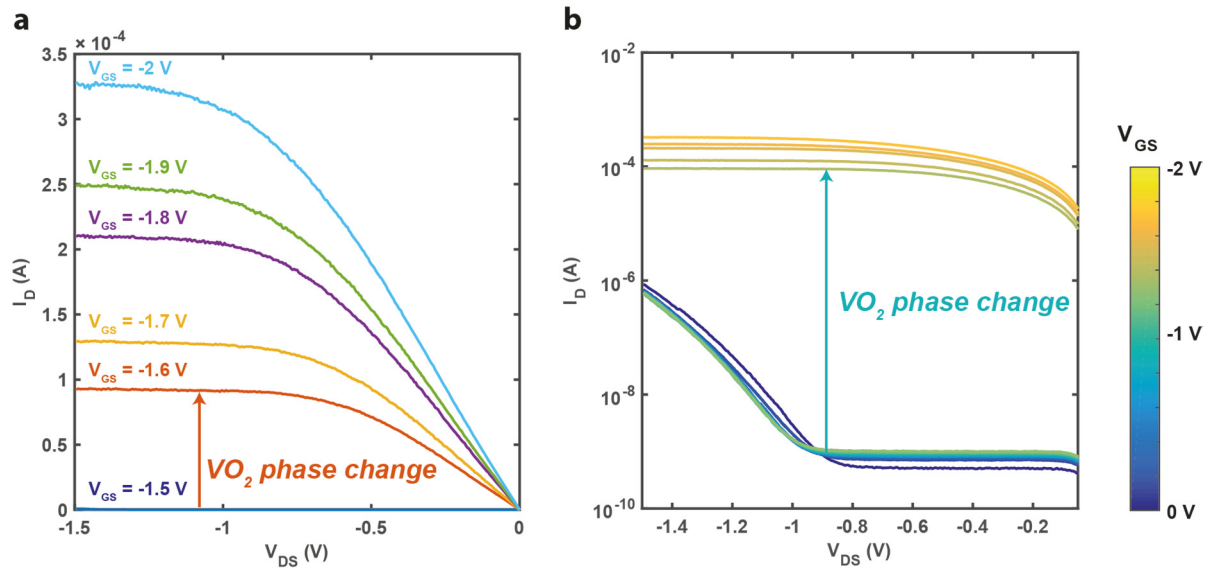
Supplementary Figure 2 | VO₂-based MIT switch. SEM image of a VO₂ switch, showing a relatively large VO₂ average grain size ~100 nm, resulting in a large and steep thermal MIT.



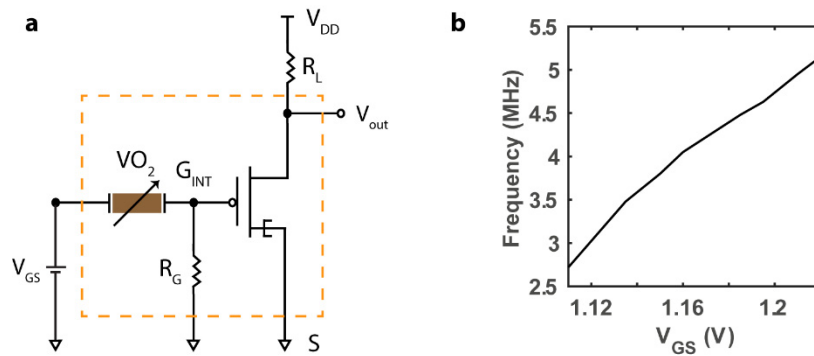
Supplementary Figure 3 | TFET gate leakage. Leakage current in the TFET used as a component for the PC-TFET for different values of drain voltage V_{DS} , ranging from -0.25 V to -1 V. Measurements performed at room temperature.



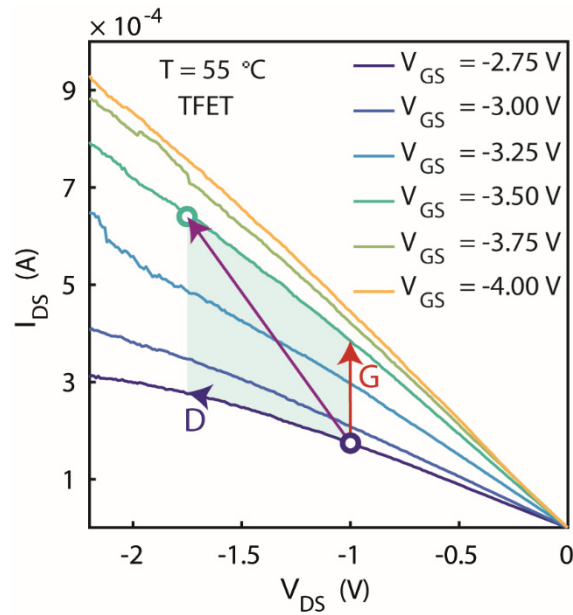
Supplementary Figure 4 | Effect of the load resistance R_L on the actuation voltage V_{GS_act} in gate configuration. I_{DS} - V_{GS} of PC-TFET in gate configuration measured at room temperature with different R_L values, ranging from 0.3 k Ω to 1 k Ω , keeping constant $V_{DS} = -0.75$ V.



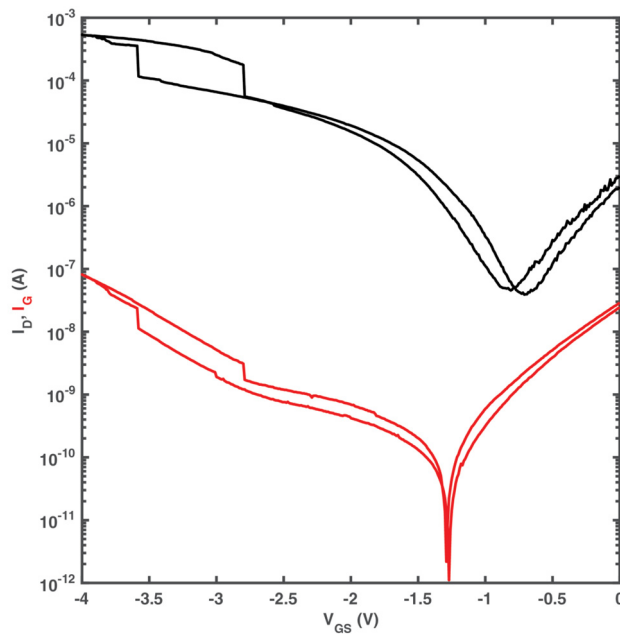
Supplementary Figure 5 | Output characteristics of PC-TFET in gate configuration. (a) Output characteristics of a PC-TFET in gate configuration for different applied V_{GS} , ranging from -0.25 V to -1 V, measured at room temperature. (b) Same output characteristics in logarithmic scale, to better show the effect of the phase change in VO_2 .



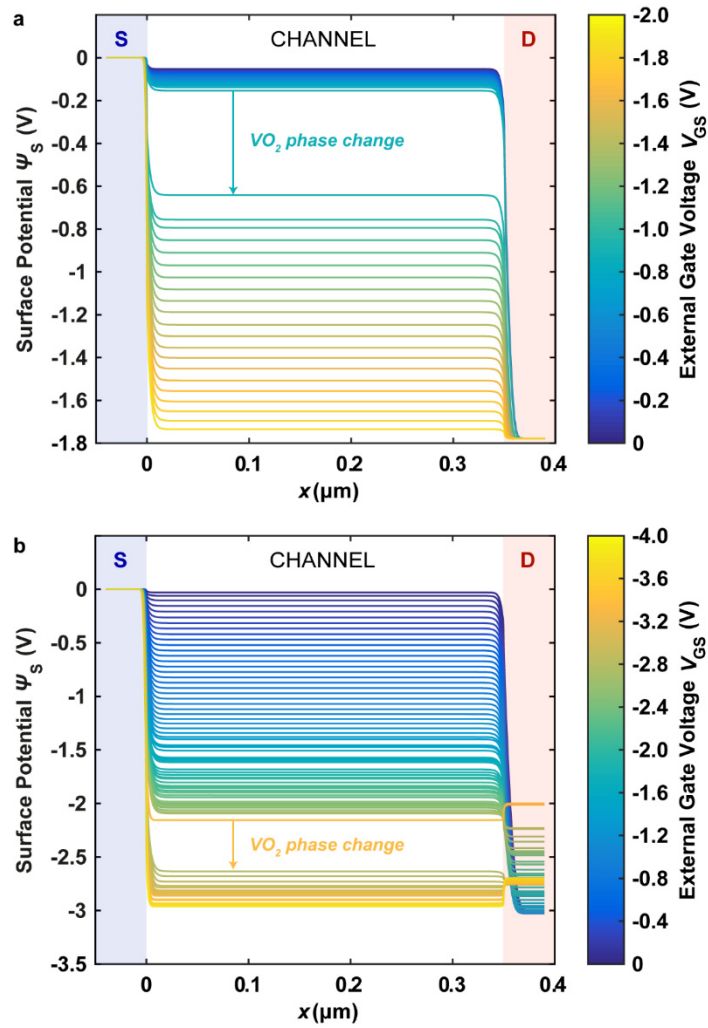
Supplementary Figure 6 | Voltage-controlled buffered oscillator based on the PC-TFET in gate configuration. (a) Circuit schematic diagram, highlighting the PC-TFET in gate configuration. The oscillation induced in the internal gate node V_{GS_INT} is read at the output V_{out} . The PC-TFET in this configuration offers a high output impedance, allowing to decouple the output load from the oscillating source. V_{GS} varied from 1.11 V to 1.22 V. $R_G = 1 \text{ k}\Omega$, $R_L = 1 \text{ k}\Omega$. $R_{VO2_OFF} = 10 \text{ k}\Omega$, $R_{VO2_ON} = 100 \text{ }\Omega$. $V_{act} = 1 \text{ V}$, VO_2 hysteresis: 0.2 V. TFET gate capacitance $C_{GS} = 50 \text{ pF}$. (b) Simulation results, showing a linear dependence of the oscillation frequency on V_{GS} , from 2.72 MHz to 5.12 MHz.



Supplementary Figure 7 | TFET output characteristics and effect of the internal voltage gains in the PC-TFET. The phase transition in VO_2 allows to switch abruptly between the two current points highlighted by a circle in the TFET output characteristics. This abrupt current increase is due to the combined effect of the gate voltage gain $G = dV_{GS_int}/dV_{GS} = 75$ (red arrow) and the drain voltage gain $D = dV_{DS_int}/dV_{GS} = 75$ (blue arrow). The values of G and D correspond to the ones measured in the PC-TFET in source configuration. Even if $G = D$, the gate voltage gain has a higher effect on the current increase.



Supplementary Figure 8 | Gate leakage for the PC-TFET in source configuration, compared to drain current. Gate leakage (red) and drain current (black) in function of V_{GS} for the PC-TFET in source configuration. Measurements performed at $T = 55 \text{ }^\circ\text{C}$ with an applied external $V_{DS} = -2 \text{ V}$. The gate leakage is negligible compared to the drain current over the whole domain of operation of the PC-TFET.



Supplementary Figure 9 | Potential cuts along the TFET channel. (a) Gate configuration. External gate voltage V_{GS} varying from 0 V to -2 V. External drain voltage $V_{DS} = -0.75$ V. Measurements performed at $T = 25$ °C. **(b)** Source configuration. External gate voltage V_{GS} varying from 0 V to -4 V. External drain voltage $V_{DS} = -2$ V. Measurements performed at $T = 55$ °C.